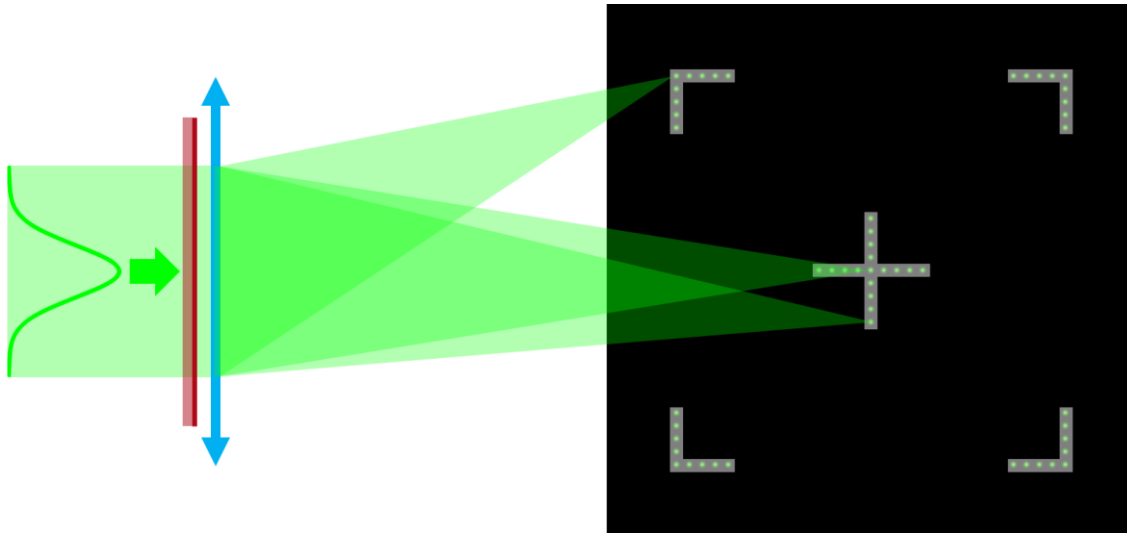


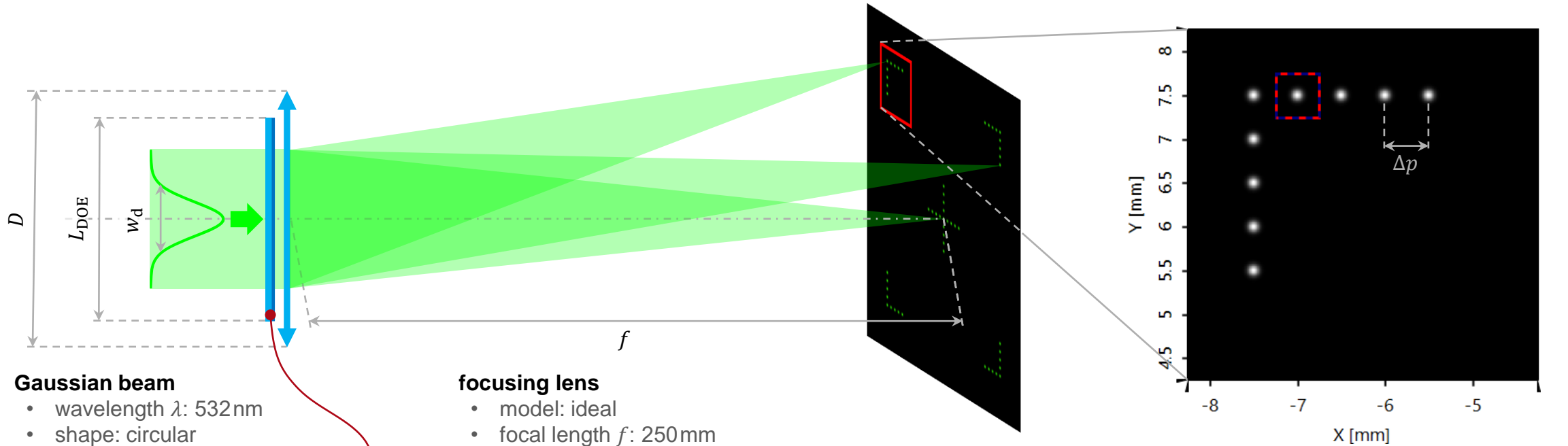
Design & Analysis of Diffractive Splitter Generating a Light Mark

Abstract



Separate (focused) beams or light points are of interest for a wide range of applications, whether for manufacturing processes, for special fiber coupling, for face recognition systems or light marker generation. Each of these applications has different and very specific requirements. VirtualLab Fusion offers you a powerful yet easy-to-use software package to design, simulate and analyze such beam splitter systems. Using a simple diffractive beam splitter system to generate a paraxial light mark, we will present a typical workflow and describe and demonstrate various design, modeling, simulation and analysis aspects that maybe relevant for such tasks.

Task



Gaussian beam

- wavelength λ : 532nm
- shape: circular
- $1/e^2$ waist diameter w_d : 1.0mm
- linearly polarized in x

focusing lens

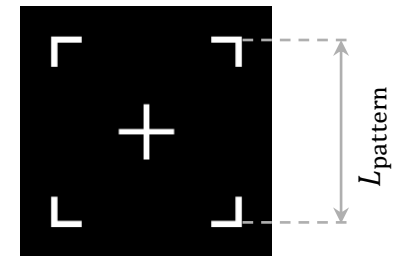
- model: ideal
- focal length f : 250mm
- shape: circular
- diameter D : 5.0mm

diffractive beam splitting element

- type: binary
- aperture shape: square
- side length L_{DOE} : 3mm
- thickness: 1mm
- substrate material: fused silica
- structure on 2nd surface
- further requirements on later slide

spot pattern to be generated

- shape: light mark with center cross and corner markings (given by bitmap file)
- distance of neighbor spot positions Δp : 500 μm
- side length L_{pattern} : 15mm
- $1/e^2$ diameter of spots: 170 μm (already given by focusing system)



Requirements

Geometry

- beam splitting element with binary structure (e.g. to reduce the cost)
- smallest feature size: $2.5\mu\text{m}$ (to ensure that the intended structure design method is within its validity range^(*))
- highest positioning accuracy: 10nm (possible capabilities of manufacturer)
- manufacturing data of mask via bitmap file

Merit Functions^(**)

The following conditions should be maintained considering an etching depth tolerance of $\pm 2\%$:

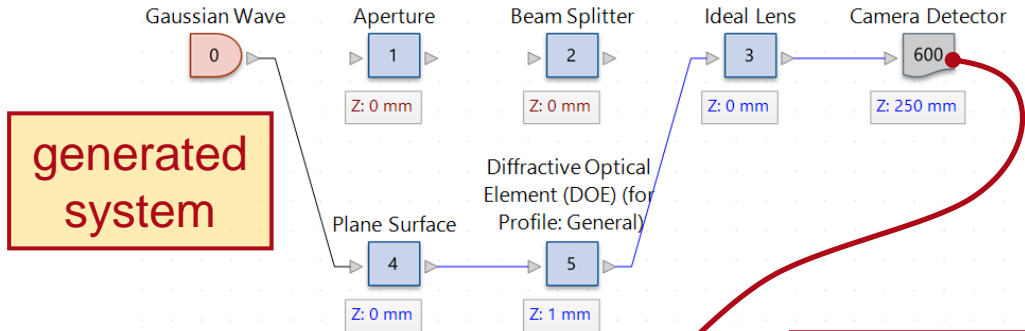
- conversion efficiency (CE) $> 60\%$
- maximum relative^(***) intensity of stray light (SL) $< 5\%$
- uniformity error (UE) $< 5\%$

() For the conversion from the functional design data to a structured data the conventional thin element approximation (TEA) is applied.*

*(**) The formulas can be found in the help/manual of VirtualLab Fusion.*

*(***) "relative" refers to the average value of the desired working orders' efficiencies.*

Result Preview



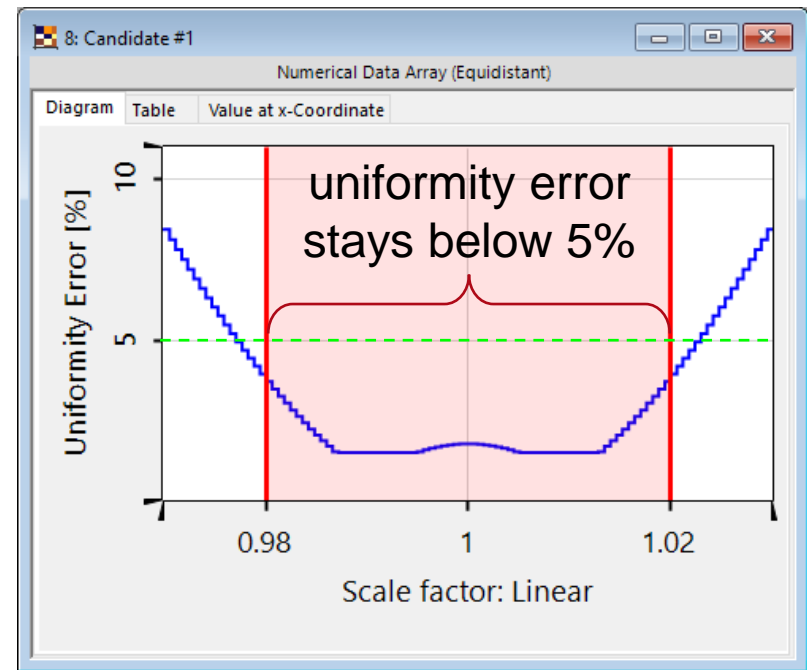
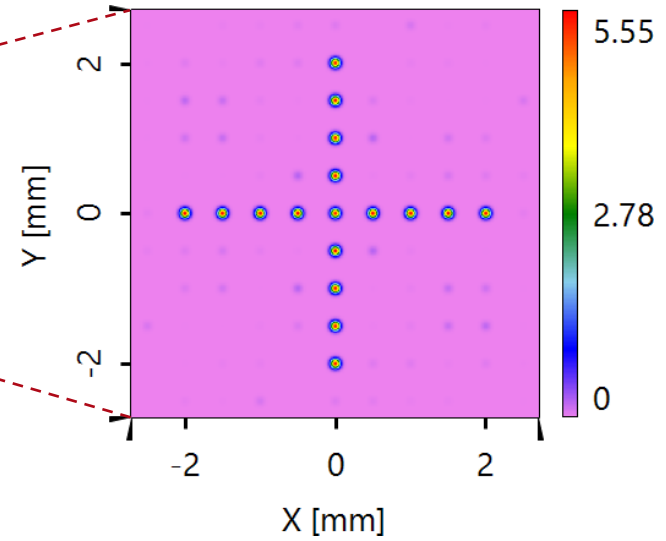
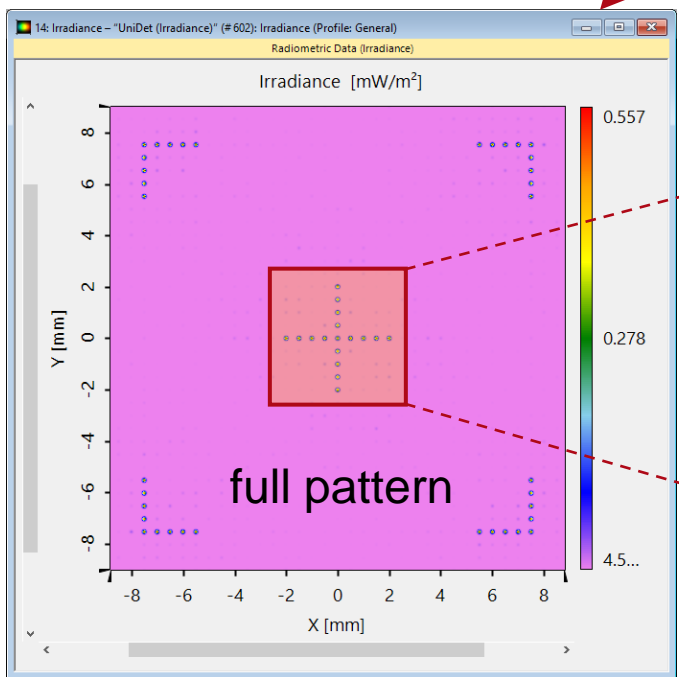
evaluated merit functions

fulfilled requirements

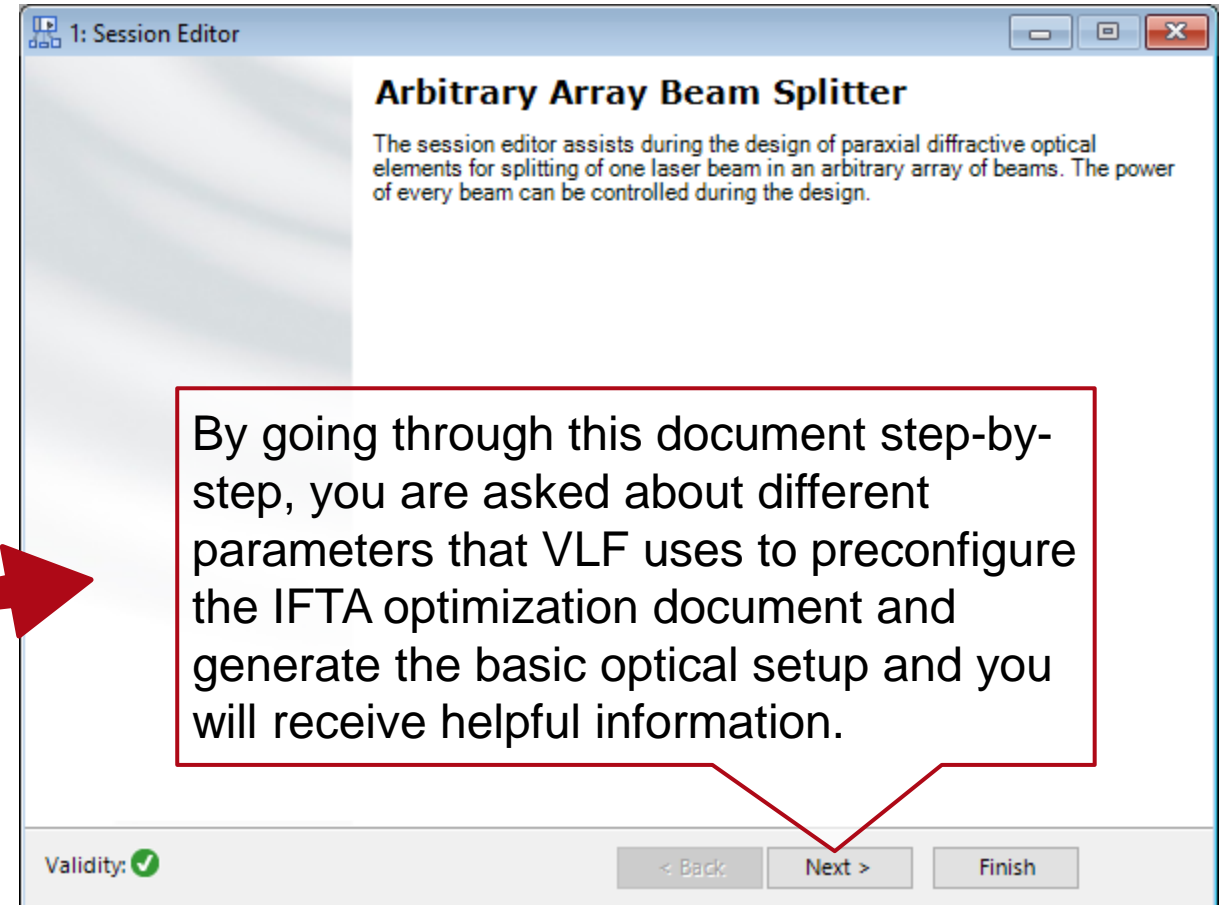
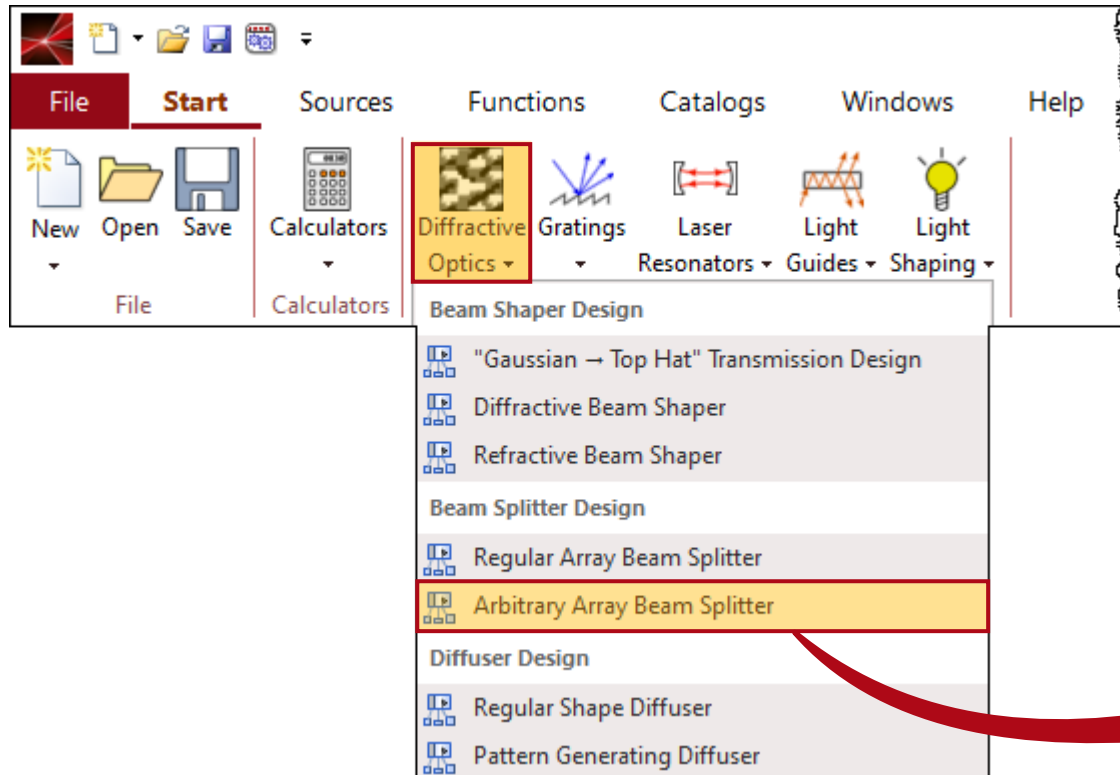
conversion efficiency ~63%
max. rel. eff. of stray light <5%

stable over tolerance range

generated irradiance pattern in false color

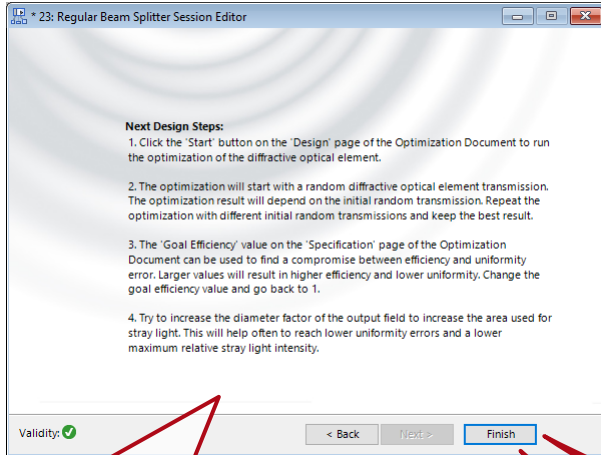


Start (Session Editor)

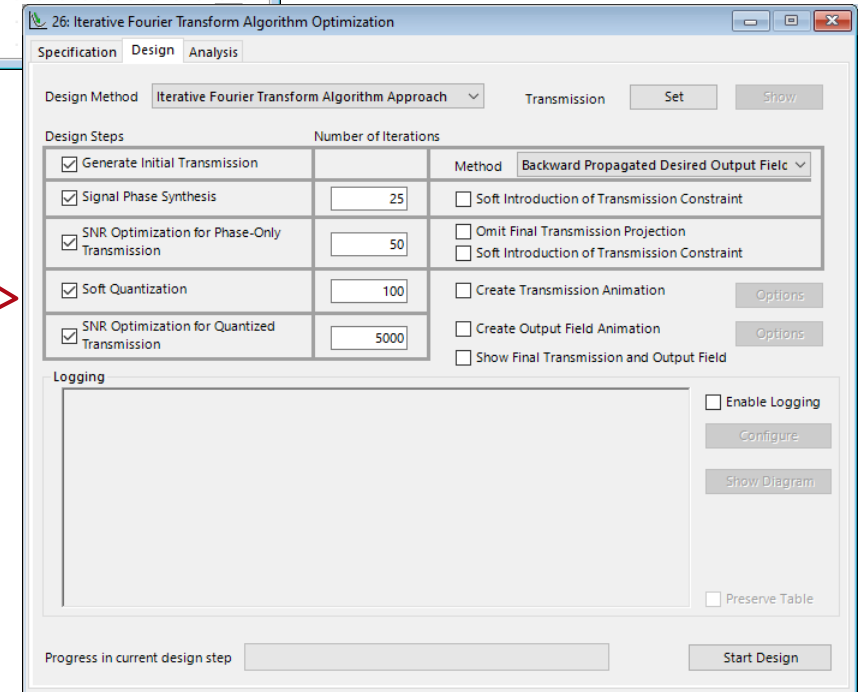
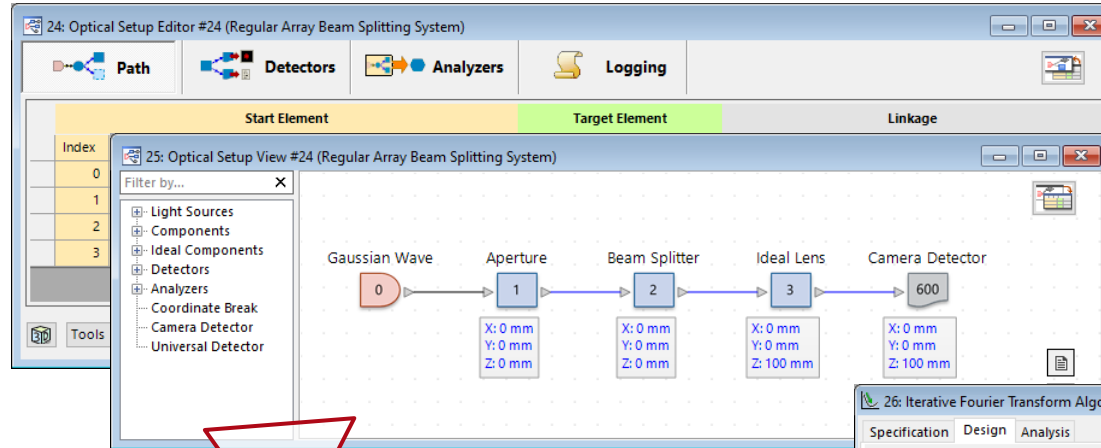


By going through this document step-by-step, you are asked about different parameters that VLF uses to preconfigure the IFTA optimization document and generate the basic optical setup and you will receive helpful information.

Presenting Preconfigured System and Design Document



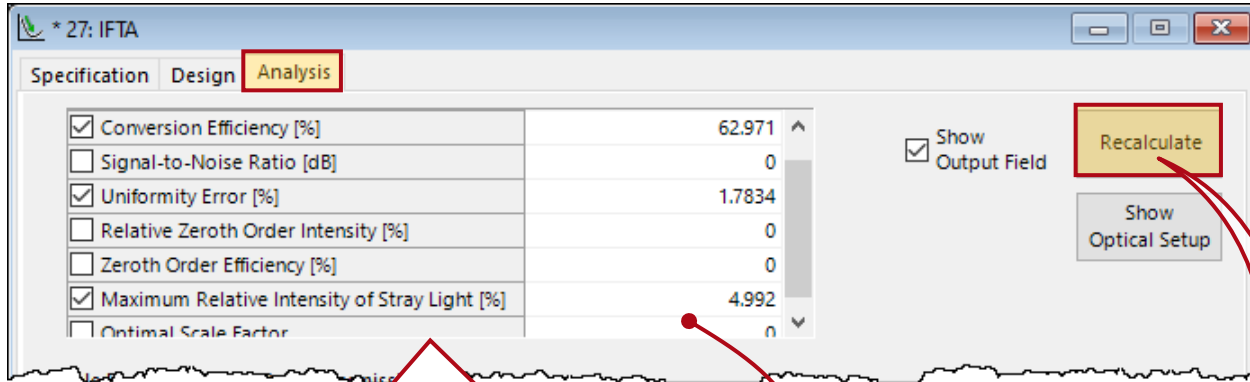
On the last page of the session editor, you will be given some tips for the next steps.



By clicking "*Finish*" in the session editor, VLF presents the user

- a preset optical setup (OS)
- a preset IFTA optimization document for the actual design and simulation.

First Impression: Light Mark & Its Merit Functions

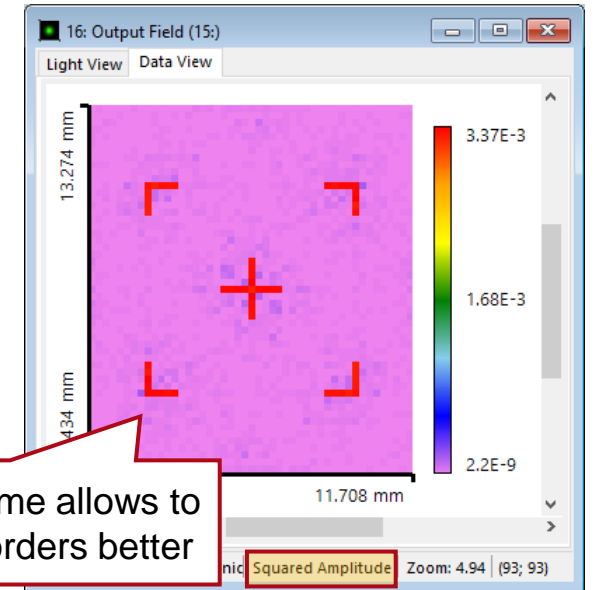
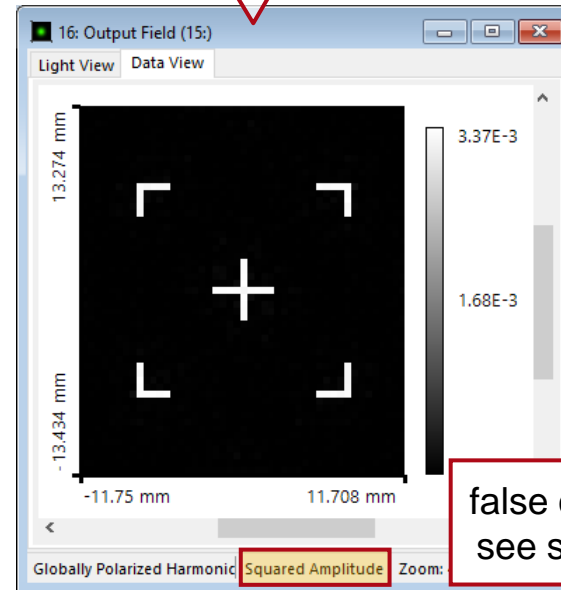


Clicking "Recalculate" on the *Analysis* tab outputs

- the checked merit function values
- the output field in its mathematical representation. For most designs, this means that each pixel of the output field corresponds to a diffraction order whose squared amplitude value is proportional to its efficiency.

No system simulation is needed for evaluating the merit functions.

Merit Function	Result Value
Conversion Efficiency (CE) / %	63.0
Uniformity Error (UE) / %	1.8
Maximum Relative Intensity of Stray Light (SL) / %	5.0



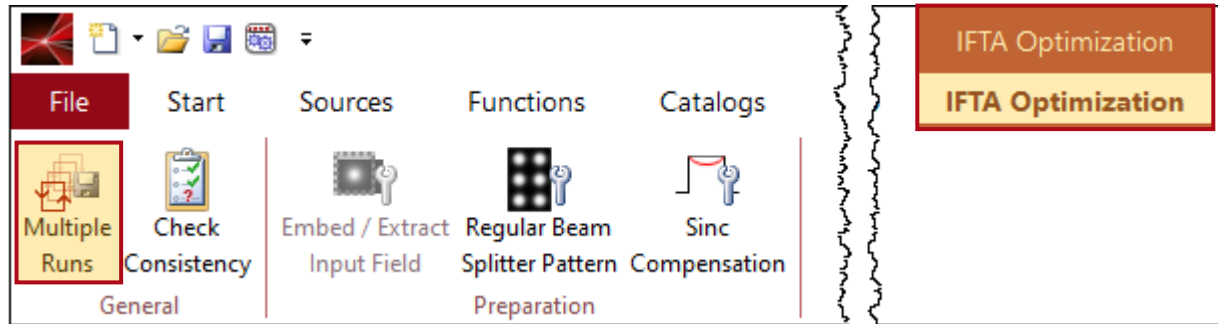
false color scheme allows to see stray light orders better

Design Selection

multiple designs and tolerance checks
with IFTA document

Multiple Run & Best Result Candidates

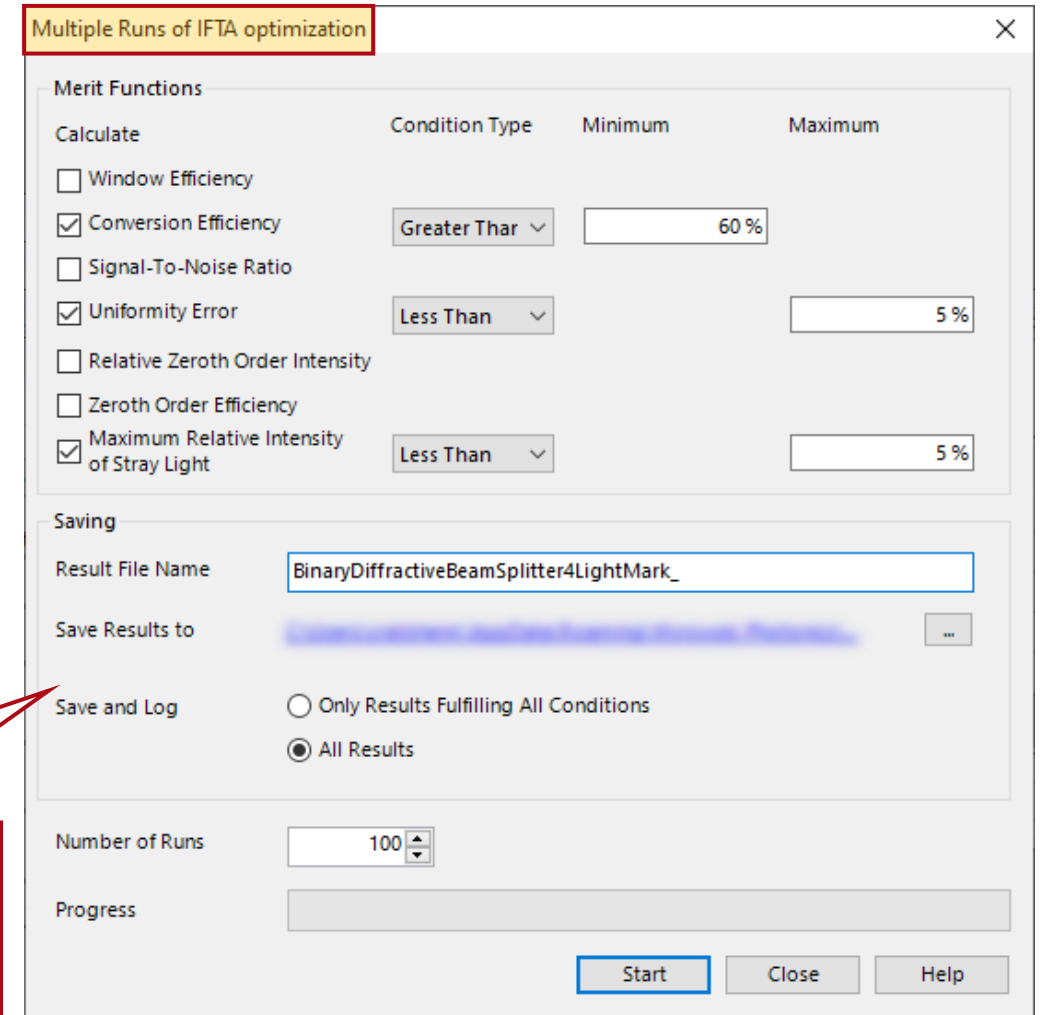
VLF offers you the *Multiple Run* document for automatic generation & evaluation of many designs with preset result filters.



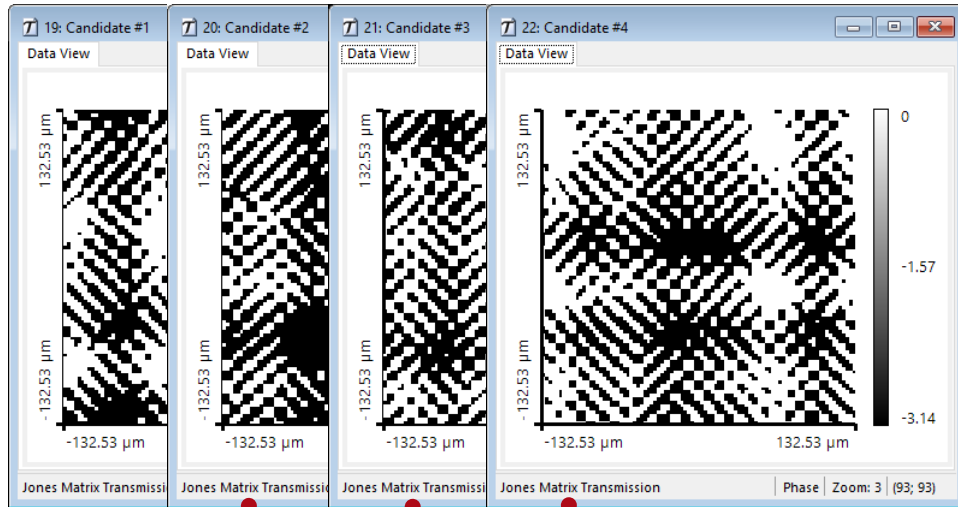
For this use case the following filters were used:

- Conversion Efficiency (CE) > 60%
- Uniformity Error (UE) < 5%
- Maximum Relative Intensity of Stray Light (SL) < 5%

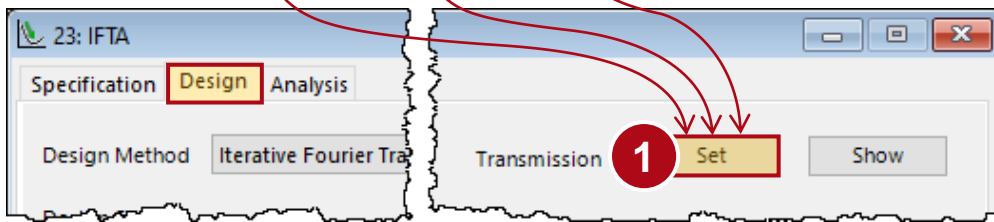
The multiple run document saves the CA2 files of the designed transmission functions together with an overview CSV file. Selected transmission functions can be set in the IFTA document for some tolerance evaluations.



Perform Tolerance Evaluations for Other Design Candidates

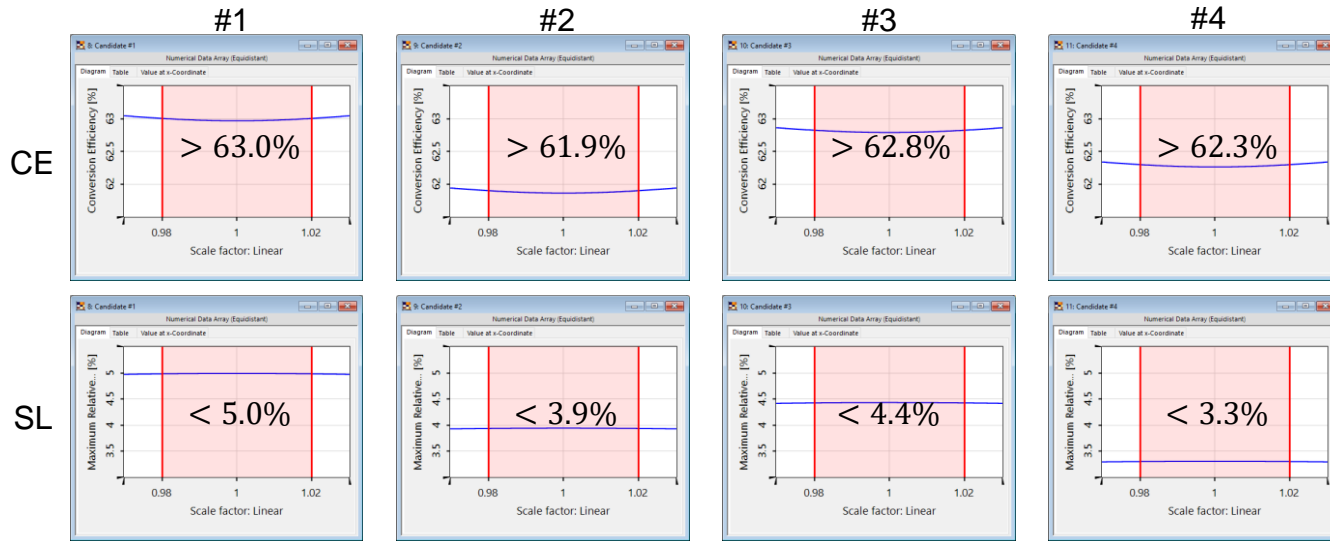


- After the transfer file of a candidate has been set on the IFTA Design tab, the robustness can be checked via the *Analysis* tab.
- The phase values are scaled from 97% to 103% (corresponding to a height deviation of $\pm 3\%$).



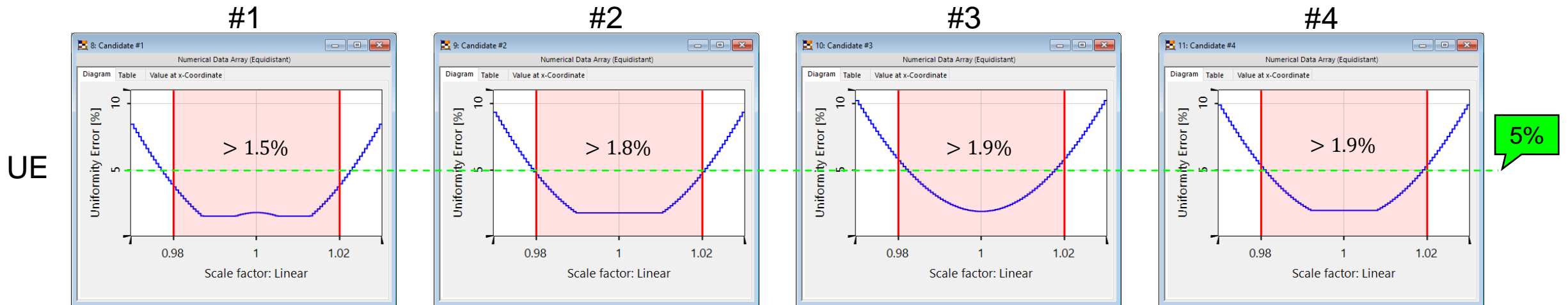
Linear	ConvEff [%]	UnifErr [%]	StrayLight [%]
1.0264	63.030673354108991	6.6133737420546357	4.978698206829808
1.027	63.033146598477664	6.9077428010704836	4.9781090630667411
1.0276	63.035653034602412	7.2068460415552025	4.97750851712136
1.0282	63.0381913768597	7.51057663527085	4.9768966742333838

Tolerance Checks & Selection of Design Candidate



The adjacent figures show the possible merit functions in case of an inaccuracy due to an etching depth tolerance ($\pm 2\%$ range is marked in red).

- The Conversion Efficiency (CE) and the Maximum Stray Light (SL) do not vary significantly. They even get better for deviating depths. **But the Uniformity Error (UE) does change for the worse!**
- Candidate #1 & #2 keep a Uniformity Error below 5%. Candidate #1 plays it safer, thus **for the following simulations candidate #1 is chosen.**



System Simulation

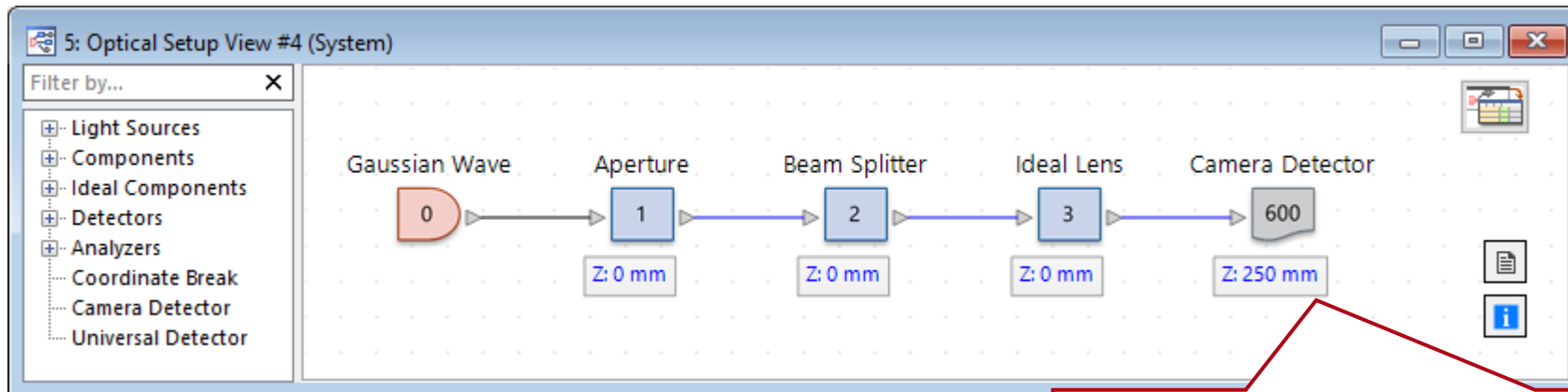
initial adjustments & first impression

Initial Optical Setup

Apart from the IFTA document, the session editor has prepared a preconfigured system, the optical setup (OS).

VirtualLab Fusion (VLF) allows to balance between speed and accuracy:

- For this scenario, the general profile simulation engine automatically selects the most accurate propagation method.
- However, we adjust the settings to use a generalized Debye integral method that provides a very good approximation result in less than 1/3 of the simulation time.

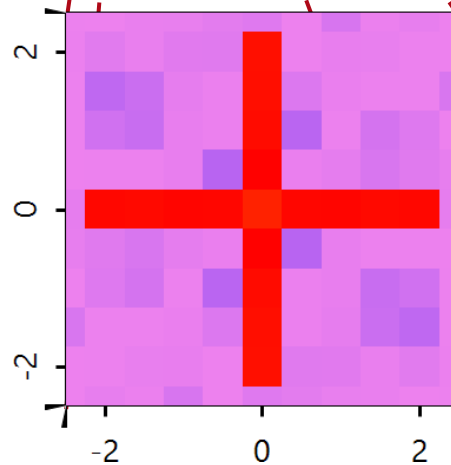
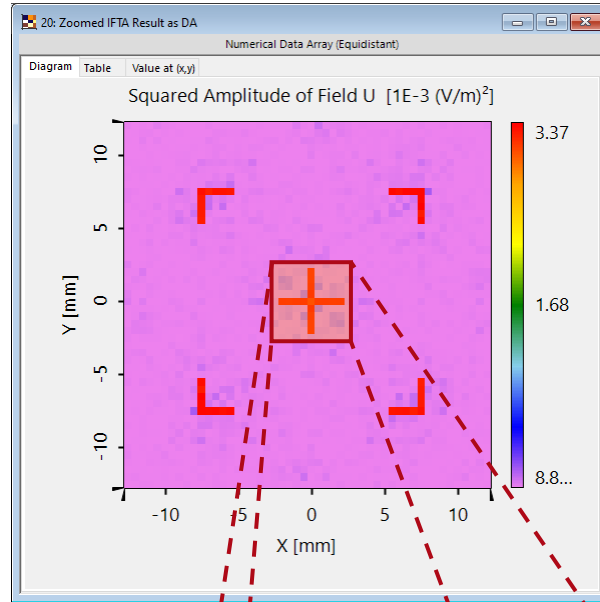


Accuracy Speed Balance (Propagation Method)

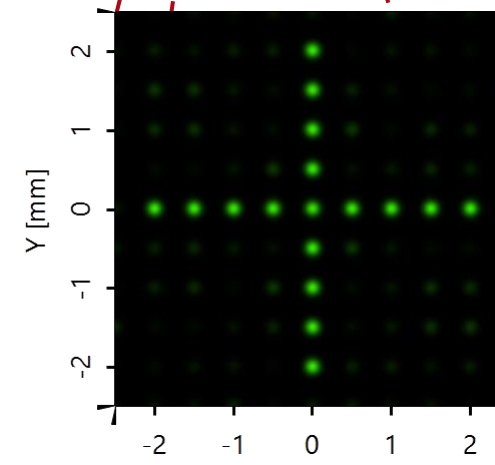
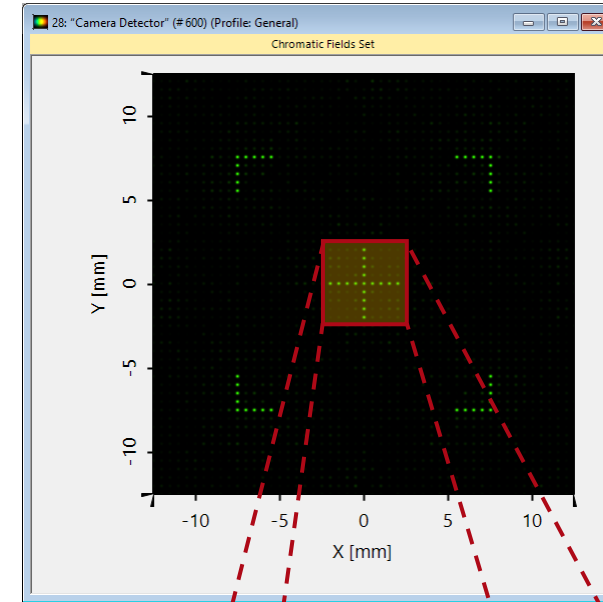
For more info follow this link into the appendix.

Result from IFTA vs System Simulation

IFTA result display
with single pixel
per diffraction order



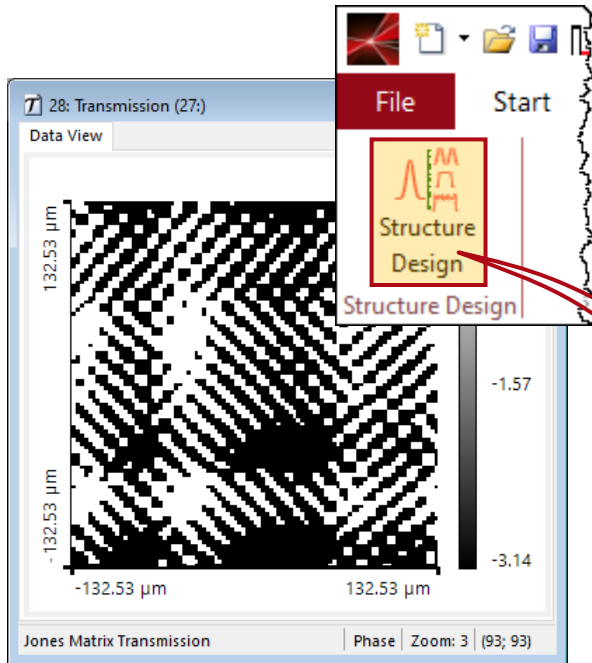
system result display
with Gaussian beams
per diffraction order



Structure Design

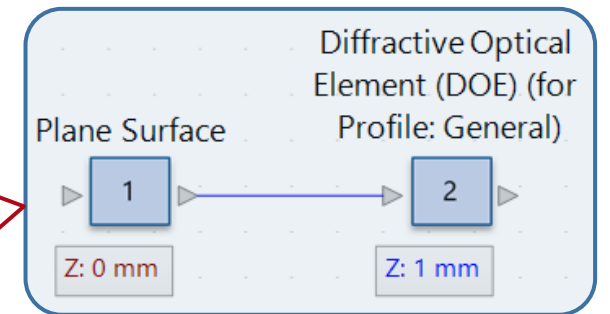
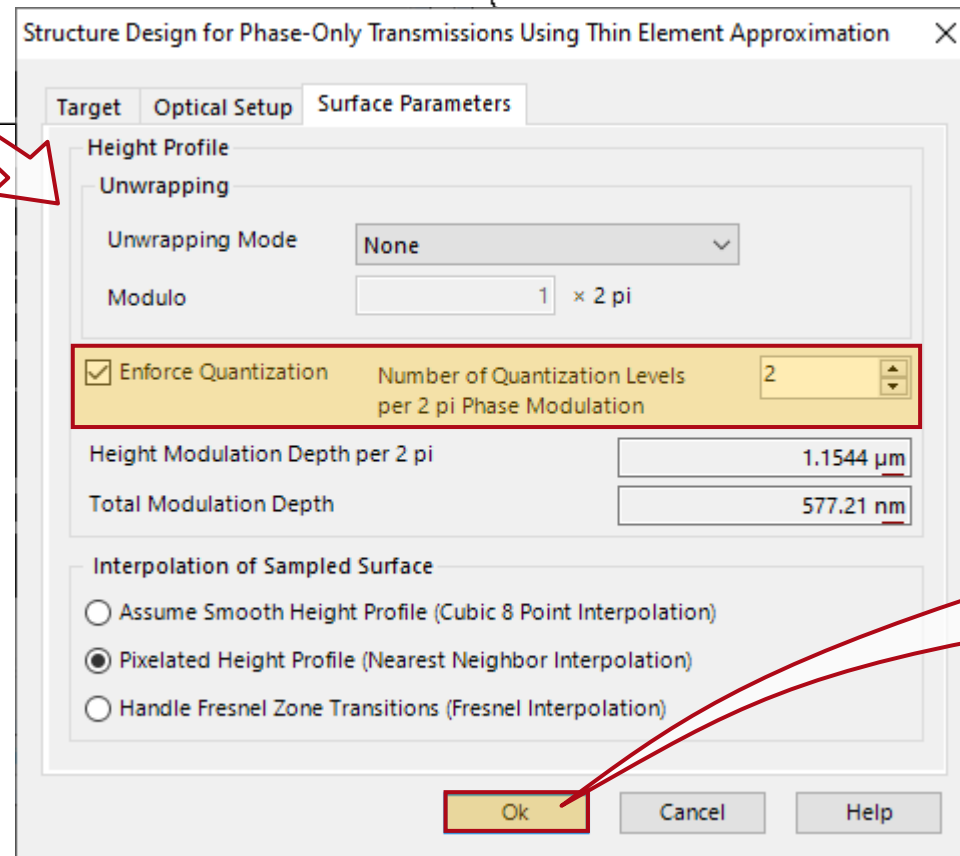
conversion of designed phase to height distribution

Structure Design



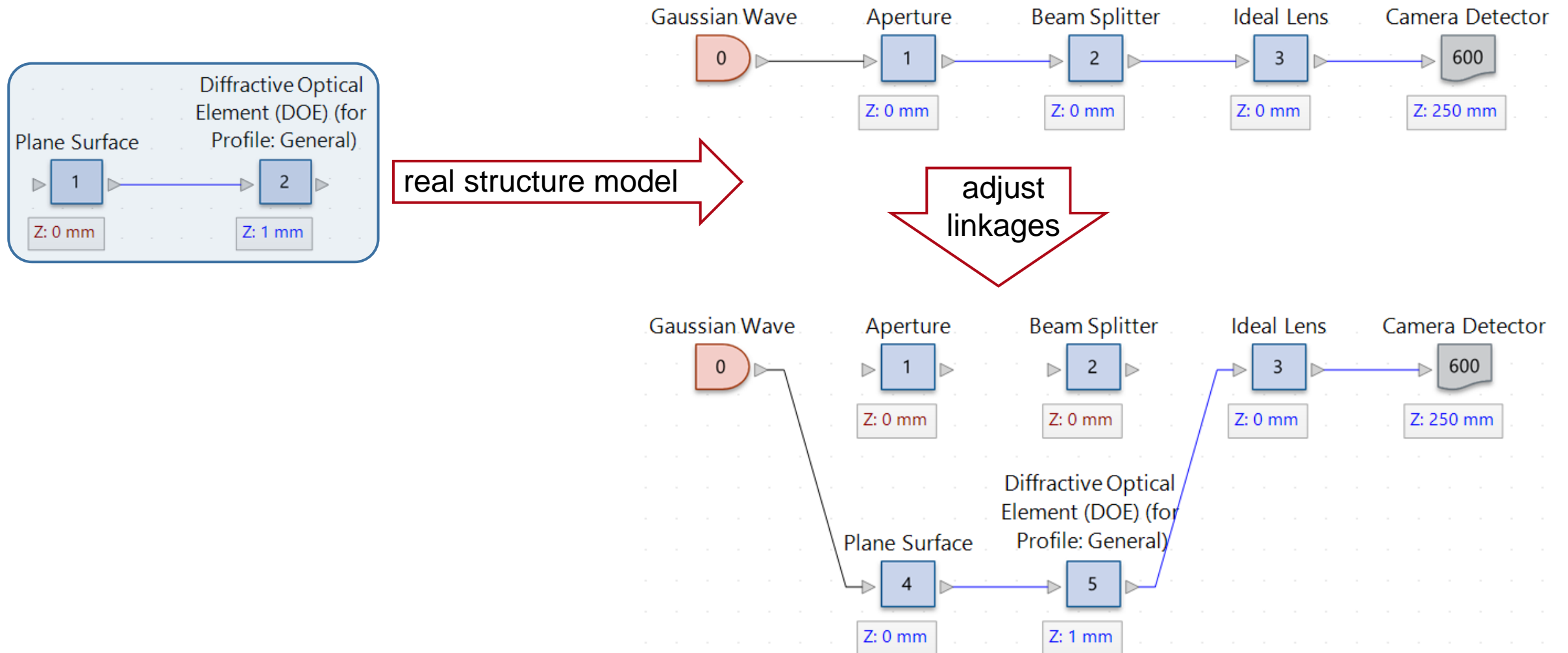
In the edit dialog for the structure design, the following configurations are applied:

- transparent plate (no mirror)
- thickness of substrate: 1 mm
- substrate material: fused silica
- embedding material: air
- design wavelength: 532 nm
- enforce quantization: 2 levels
- pixelated height profile

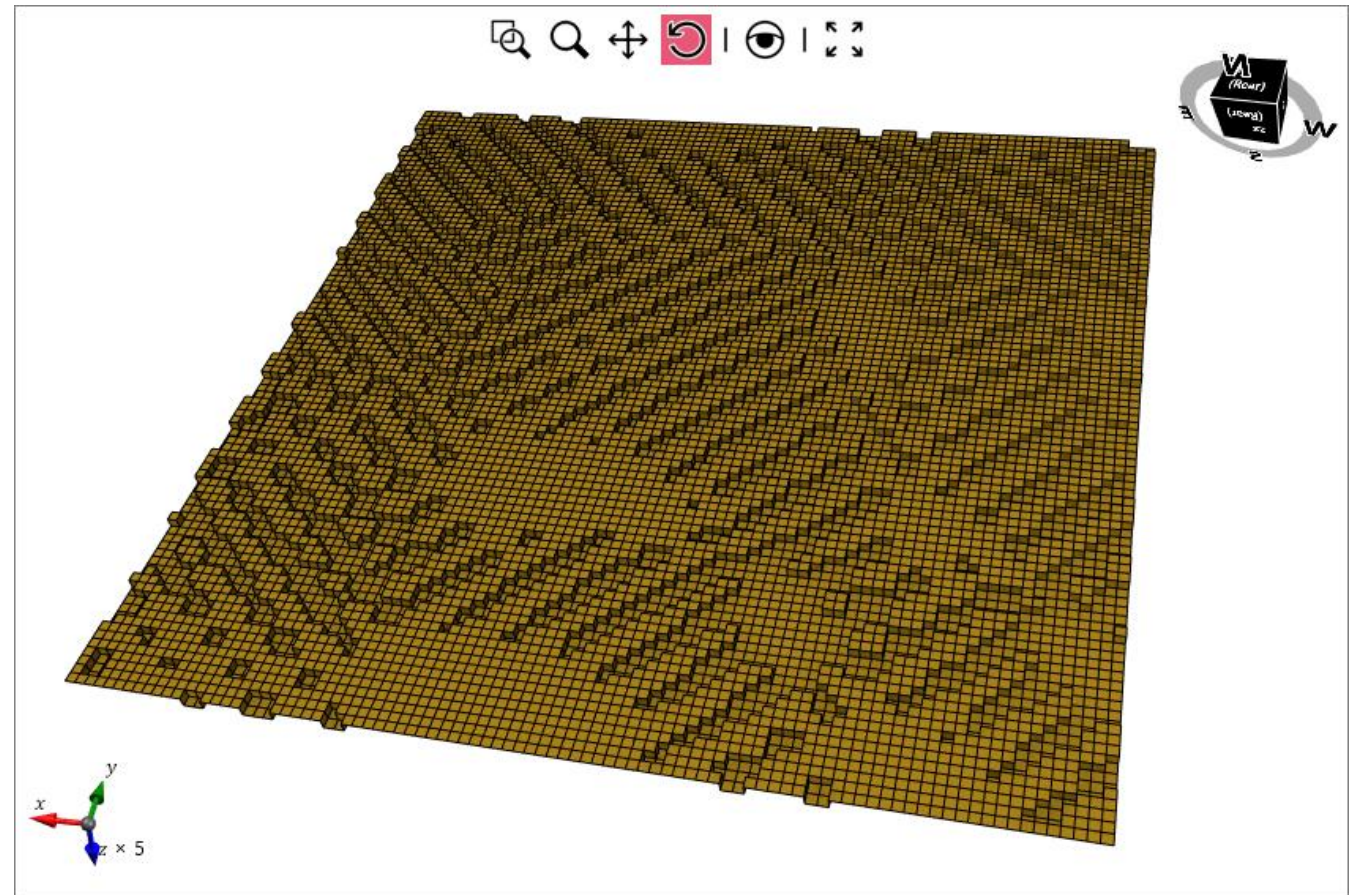
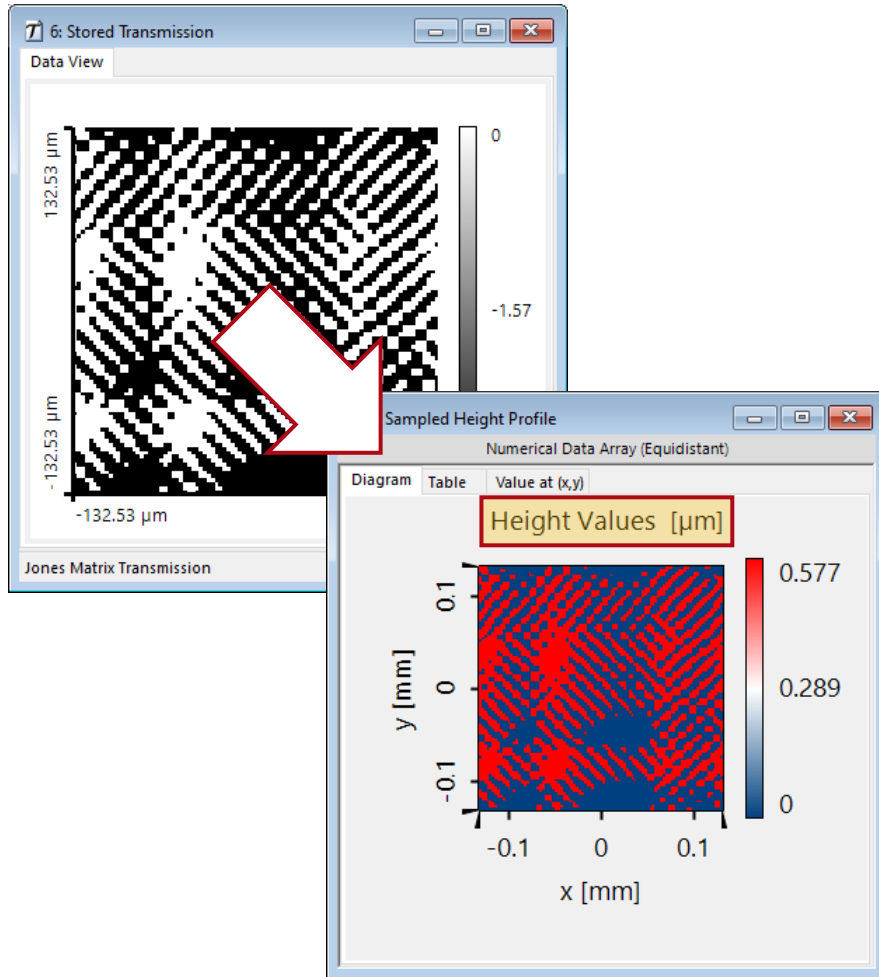


real model of diffractive
binary beam splitter
(with 2 surfaces and material)

Integrate Real Splitter Model to System

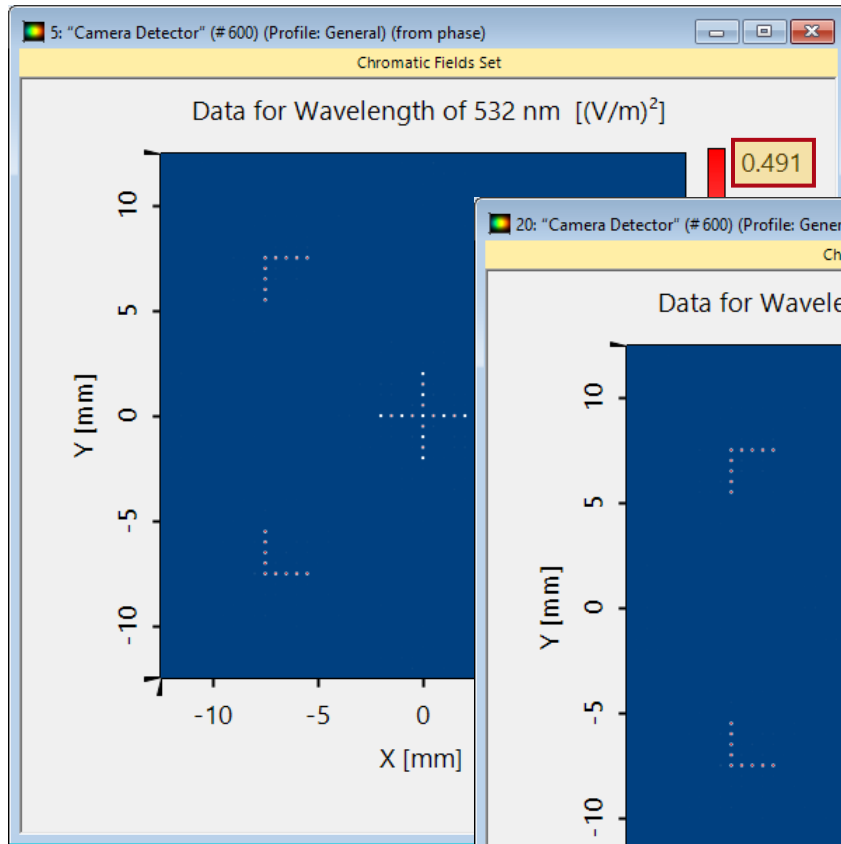


Structure Representation

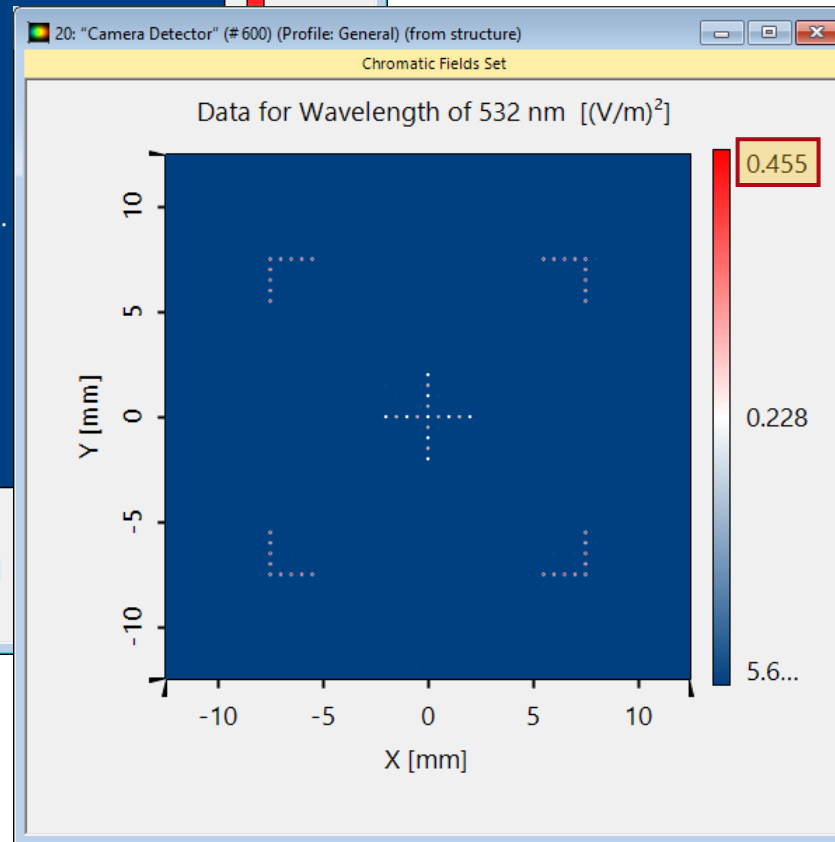


for clearer view of height structure,
the modulation depth was scaled by a factor of 5

Simulation Difference for Phase vs Structure: Fresnel Effects



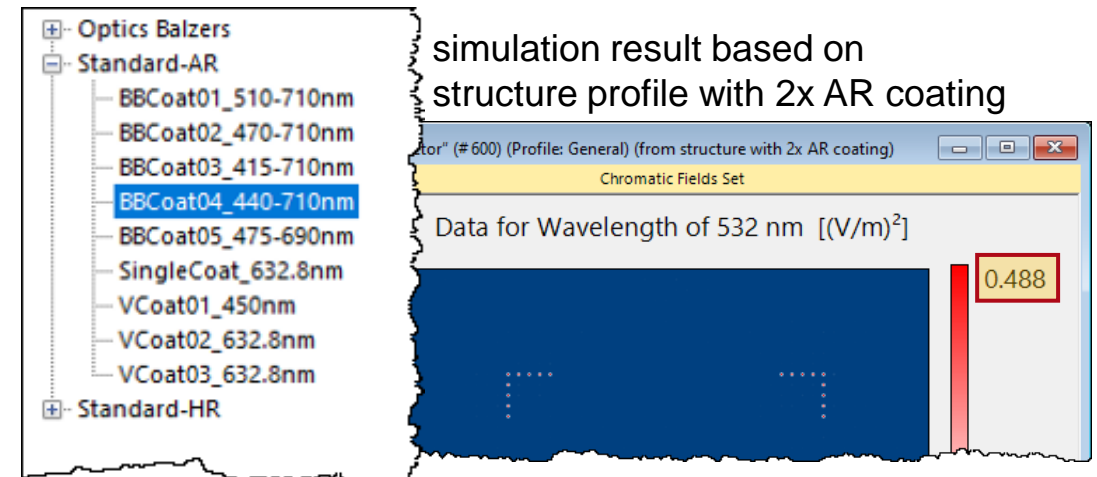
simulation result based on phase function



simulation result based on structure profile

In the simulation using real structures and materials effects like Fresnel reflection can be considered.

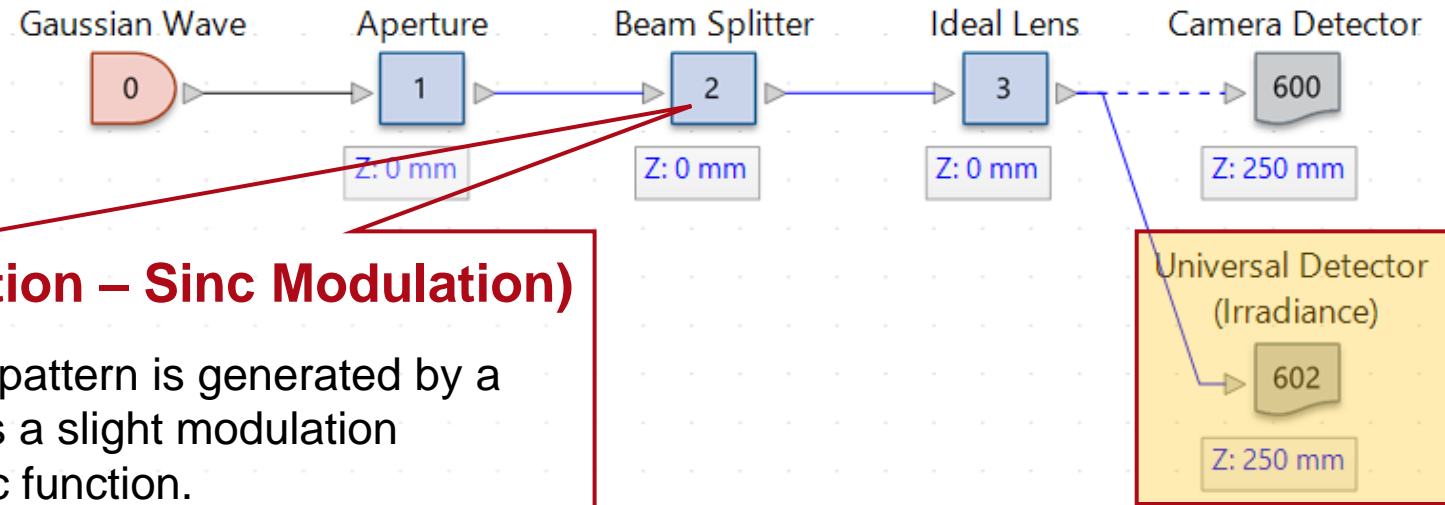
- Adjacent figures show, that the maximum in the result based on the phase function (0.491 (V/m)^2) is higher than the result's maximum from the structure simulation (0.461 (V/m)^2).
- Typically, you would apply anti reflection (AR) coatings to reduce this effect.
- By applying the AR coating BBCoat04_440-710nm from VLF's catalog, the reflection losses are gone.



Final System Simulations

pixelation factor and irradiance detection

Final Adjustments to the System



Accuracy Speed Balance (Pixelation – Sinc Modulation)

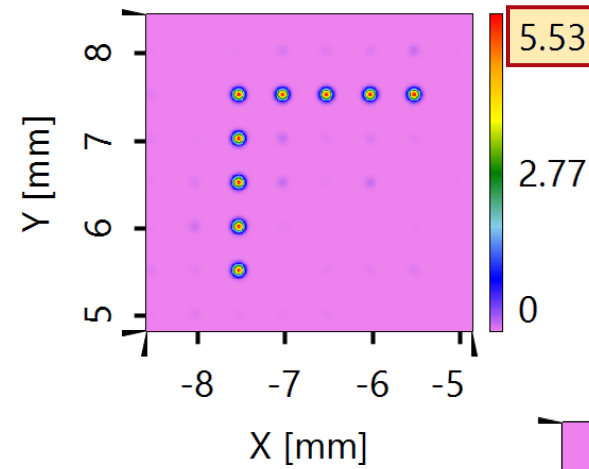
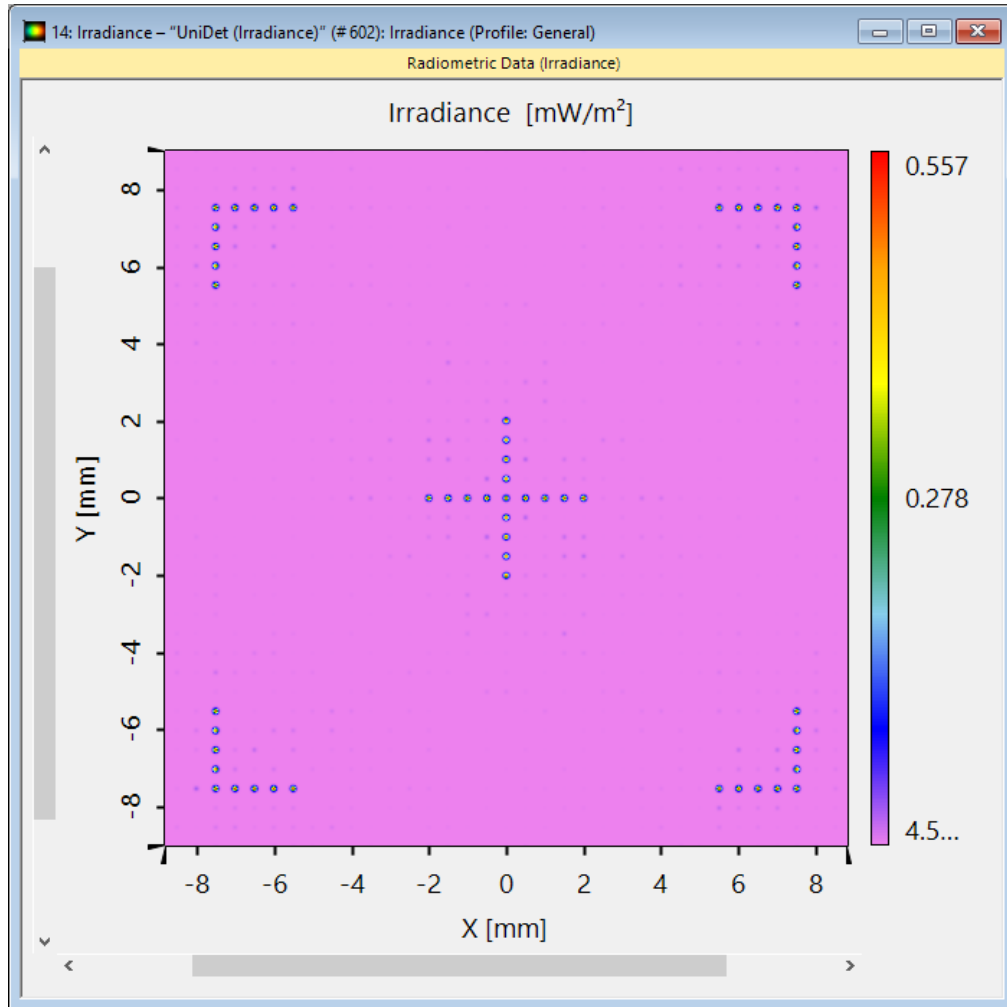
- There exists a physical effect, that if a pattern is generated by a pixelated structure, the pattern exhibits a slight modulation according to the center region of a sinc function.
- This effect will be considered in the simulation if the so-called pixelation factor is set larger than the default 1×1 .
- For the final simulation we used a pixelation factor of 5×5 .
- This increases the simulation duration but also the accuracy. So, again, VLF offers the customer the option to get quick first results and to include more physics by increasing the accuracy.

[For more info follow this link into the appendix.](#)

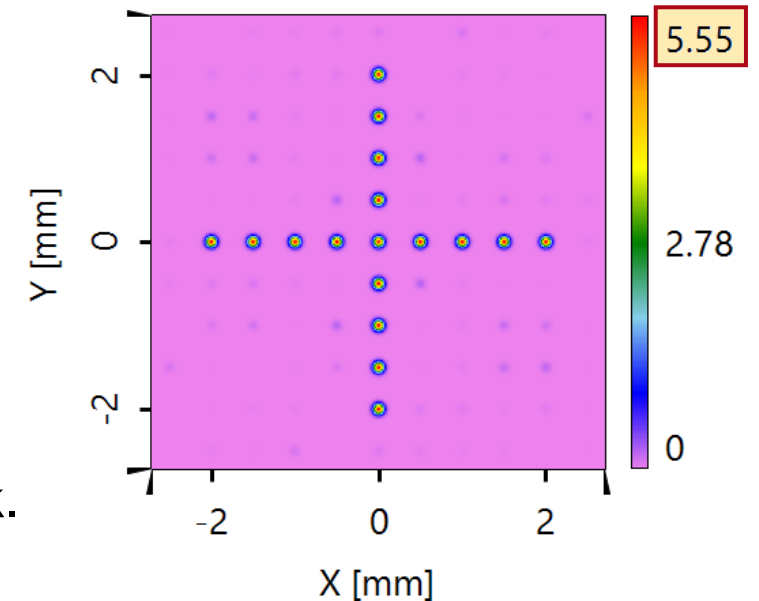
For the final evaluation we use the universal detector calculating the irradiance.

[For more info follow this link into the appendix.](#)

Irradiance Results from Simulation with Pixelation Factor of 5x5



This final simulation result shows very nicely the uniform spots achieved along the desired light mark.



Structure Export

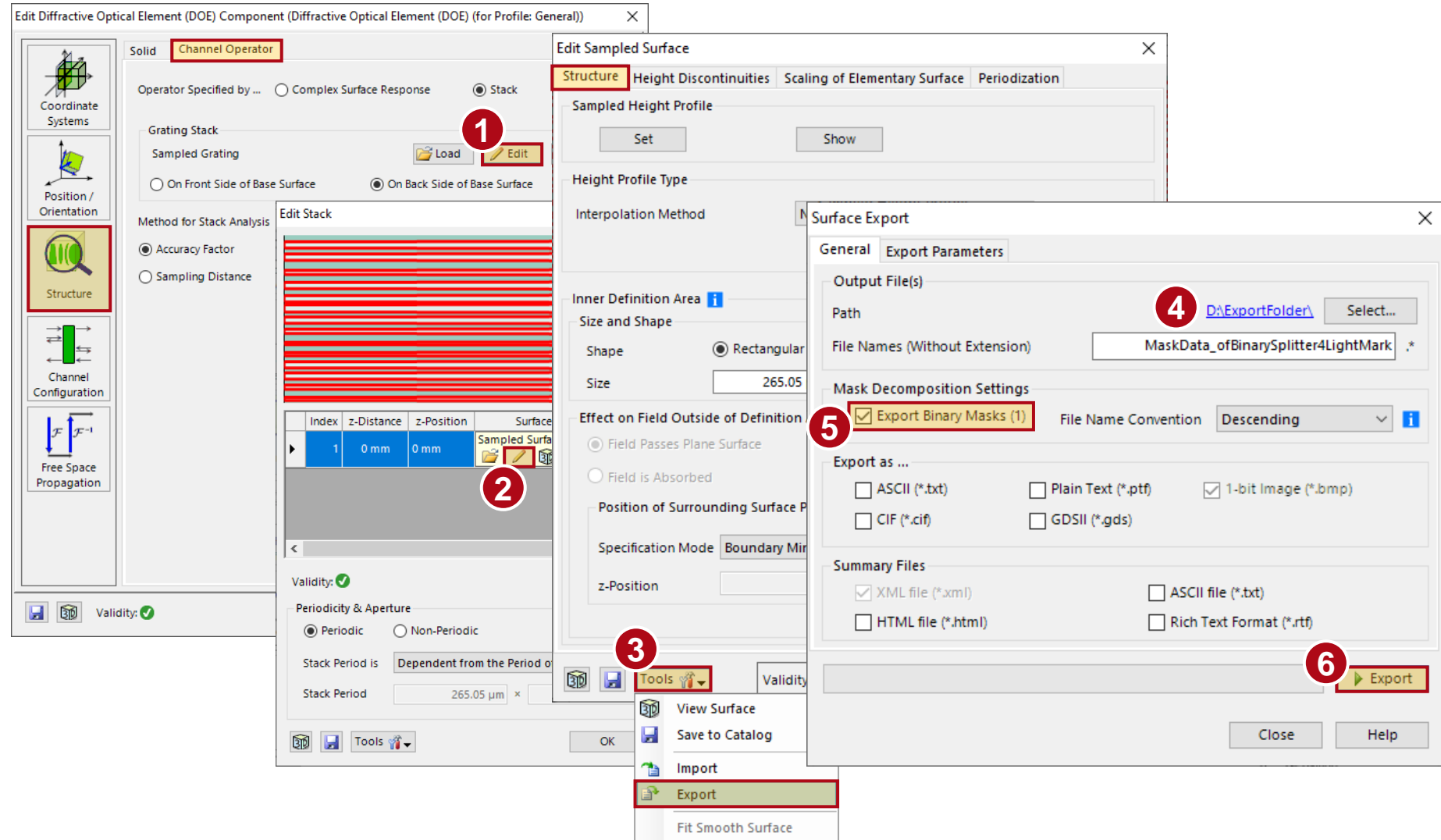
generate data for manufacturer

Export of Fabrication Data

The export is initiated directly from the surface edit dialog via the *Tools* button.

The export dialog provides the user with various options.

VLF will always generate a summary file which contains all relevant description for the manufacturer.



Exported Data

Surface Parameters

Parameter	Value
Aperture Size:	(2.6505 mm, 2.6505 mm)

The height definition is based on the coordinate system of the surface.

exported BMP of mask data

Additional Metadata for Sampled Surface

Surface Parameters	
Parameter	Value
Aperture Size:	(2.6505 mm, 2.6505 mm)
Aperture Shape:	Rectangular
Height Outside Element:	0 mm
Absorbing Material Outside Inner Definition Area:	No

Element Parameters

Parameter	Value
Total Profile Height:	577.2080155 nm
Number of Height Levels:	2
Height Level Difference:	577.2080155 nm
Exported Binary Masks:	Yes
Pixel Size:	(2.85 μm, 2.85 μm)
Number of Exported Pixels:	(930, 930)
Exported Element Size:	(2.6505 mm, 2.6505 mm)
Data Represents Only One Period:	No

Mask Information

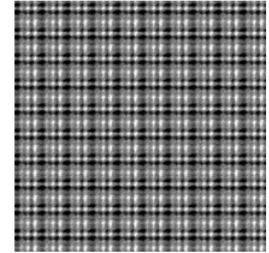
Parameter	Value
Number of Masks:	1
Height Modulation of Mask #1:	577.2080155 nm

Specific Export Settings

Parameter	Value
Invert Heights:	No

Mask 1

Type	File Name
Bitmap File:	MaskData_ofBinarySplitter4LightMask.bmp



export summary in HTML format

This metadata file was created with VirtualLab 2023.2.2 on 2024-01-15 and is valid for surfaces (pixelated export).

Document Information

title	Design & Analysis of Diffractive Splitter Generating a Light Mark
document code	DOE.0002
document version	3.0
required packages	<ul style="list-style-type: none">• Diffractive Optics
software version	2023.2 (2.30)
category	Application Use Case
further reading	

Appendix

Info & Adjustments of Initially Output Optical Setup

The image displays three windows from OpticStudio. The top window, 'Optical Setup View #4 (System)', shows a ray path starting with a Gaussian Wave (0), passing through an Aperture (1) at Z: 0 mm, a Beam Splitter (2) at Z: 0 mm, an Ideal Lens (3) at Z: 0 mm, and ending at a Camera Detector (600) at Z: 250 mm. A red circle with the number '2' points to the Camera Detector. The middle window, 'Optical Setup Editor #4 (System)', contains a table with the following data:

Start Element				Target Element		Linkage		
Index	Element Name	Ref. Type	Medium	Index	Element Name	Modeling Profile	On/Off	Color
0	Gaussian Wave	-	Standard Air in Homogen...	1	Aperture	General Profile	On	—
1	Aperture	T	Standard Air in Homogen...	2	Beam Splitter	General Profile	On	—
2	Beam Splitter	T	Standard Air in Homogen...	3	Ideal Lens	General Profile	On	—
3	Ideal Lens	T	Standard Air in Homogen...					

Below the table, a dropdown menu for the 'Simulation Engine' is open, showing options: Profile: General (selected), Profile: Ray Results, Profile: General, and Classic Field Tracing. A red circle with the number '1' points to this menu. The right window, 'Edit Camera Detector', shows the 'Fourier Transforms' tab with the following settings:

Type of Fourier Transform	Source to Detector	Component to Detector
Forward FFT	<input type="checkbox"/>	<input type="checkbox"/>
Forward SFT	<input type="checkbox"/>	<input type="checkbox"/>
Forward PFT	<input checked="" type="checkbox"/>	<input checked="" type="checkbox"/>
Inverse FFT	<input type="checkbox"/>	<input checked="" type="checkbox"/>
Inverse SFT	<input type="checkbox"/>	<input checked="" type="checkbox"/>
Inverse PFT	<input checked="" type="checkbox"/>	<input checked="" type="checkbox"/>

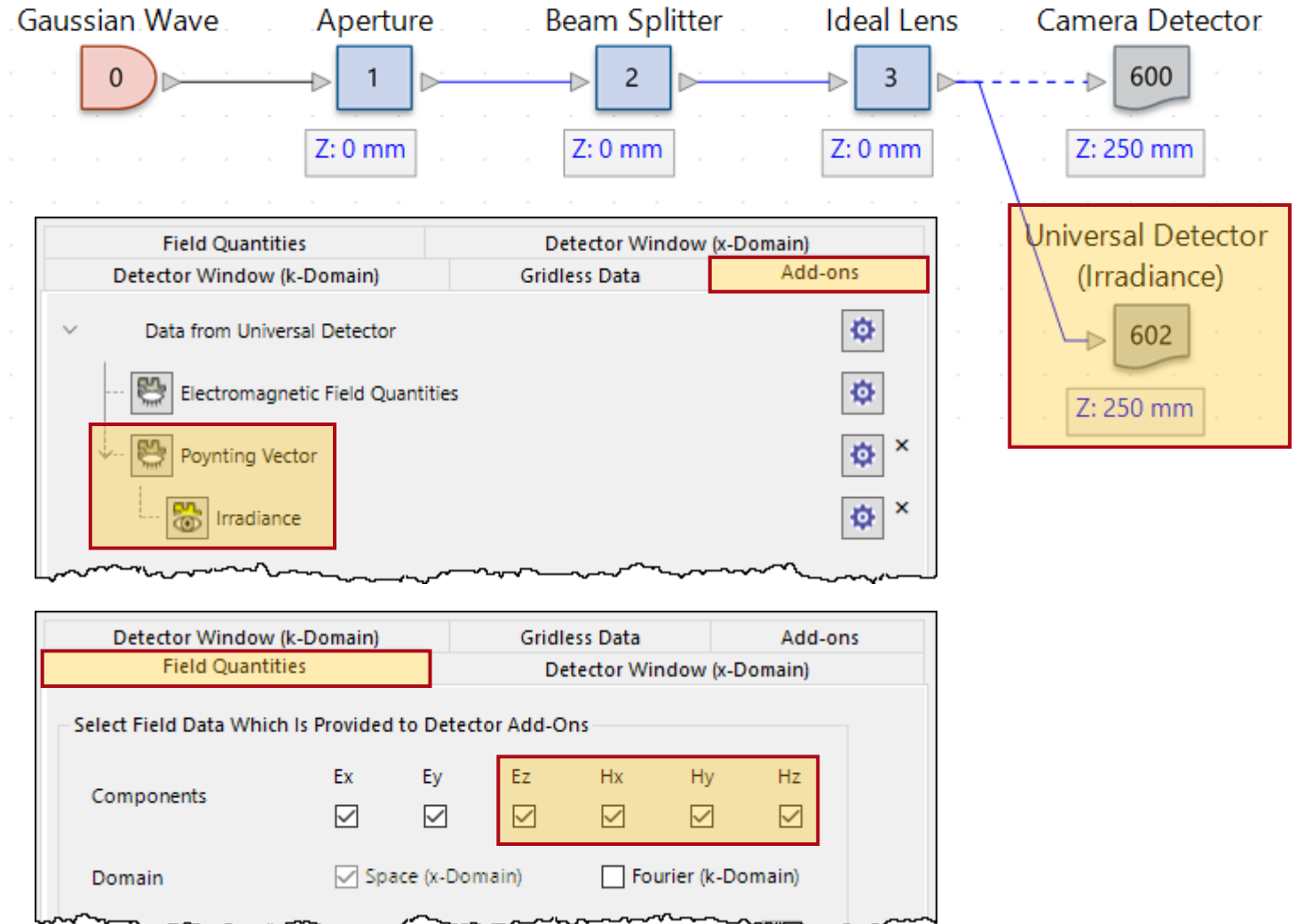
Other settings in the dialog include: Automatic PFT Selection Accuracy Level (0), Resulting Pointwise Transformation Index (PTI) Threshold (1), Enforce PFT Beyond 10000 Sampling Values? (No), and PFT for Bijective Mapping Only? (No). A red box highlights the 'Free Space Propagation' option in the left sidebar.

1. Currently the preset simulation engine is still "Classic Field Tracing (CFT)", but the newer General Profile option is already the better choice for most setups. Thus, the simulation engine is switched to "Profile: General".
2. Furthermore, as this scenario can be assumed to be paraxial, where we do not expect distorted off-axis spots, and the light is propagated into a Fourier plane, we choose the Fourier transforms "pointwise" & "inverse integral"; this corresponds to the generalized Debye method. *By default, the automatisms of VLF with version 2023.2 (build 2.30) are a bit stricter and would select a rigorous propagation method which would take about 3x longer, with similar result.*

question of
balance
between speed
and accuracy

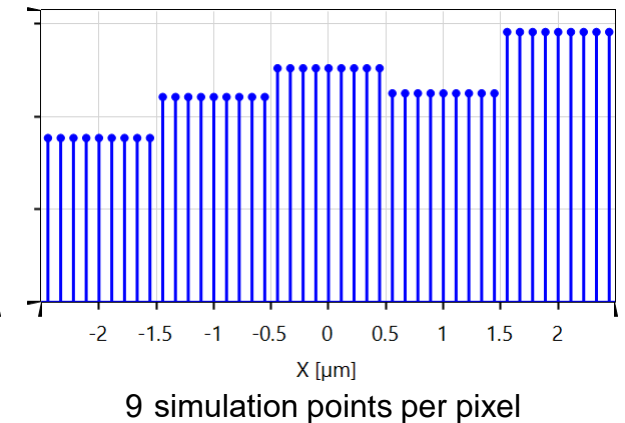
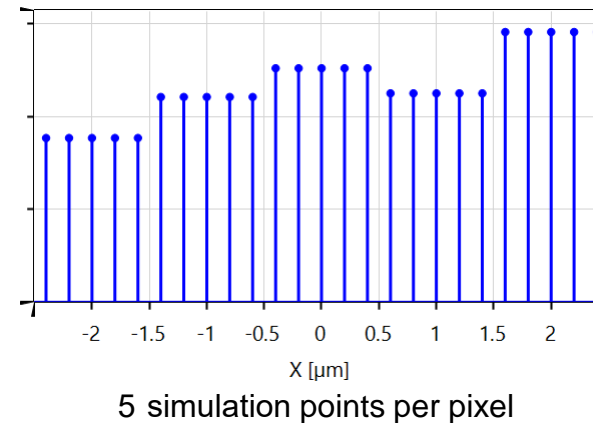
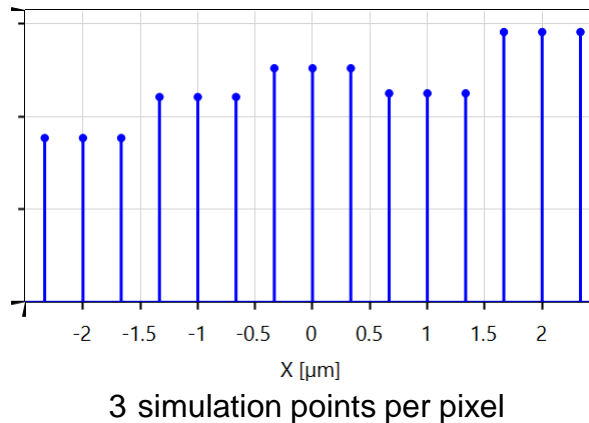
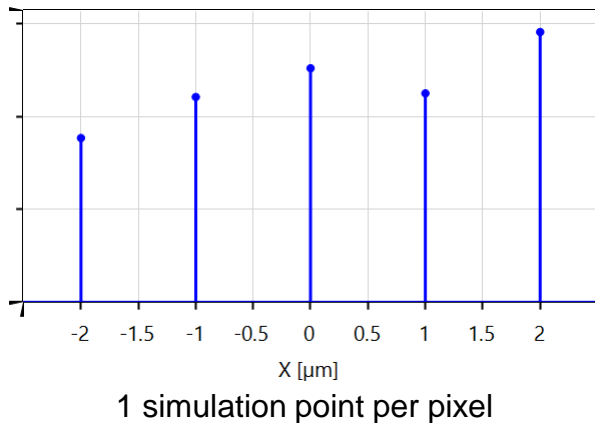
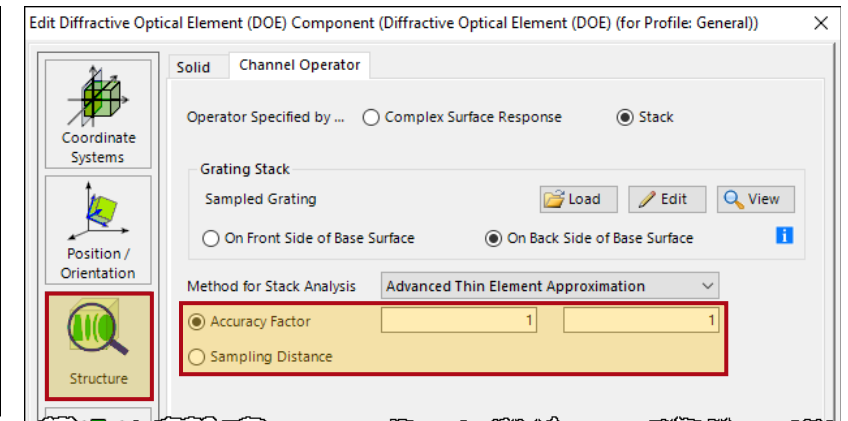
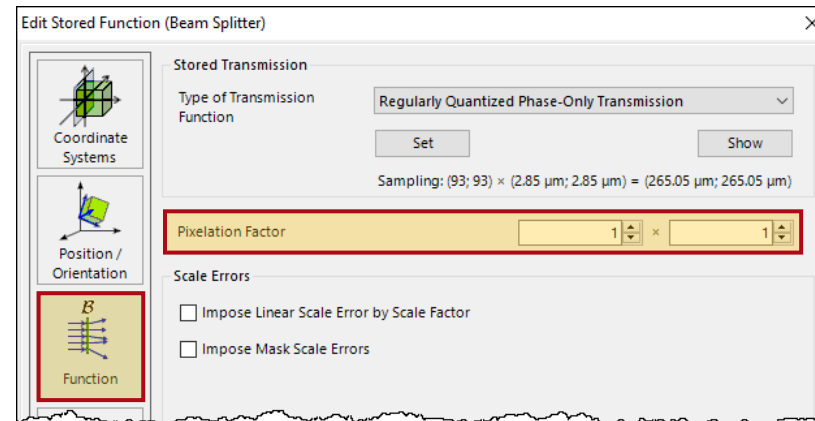
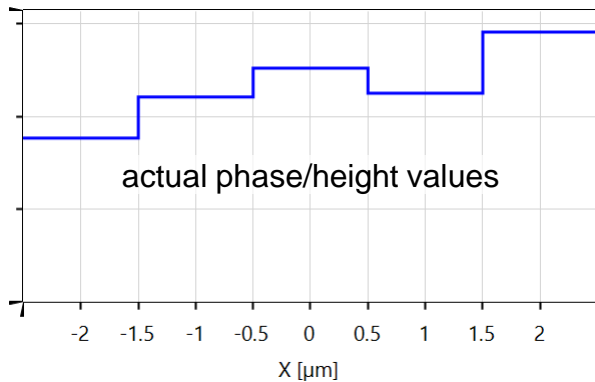
Configuring of Radiometric Evaluation

- The camera detector outputs the components of the \mathbf{E} field. Typically, one is interested in radiometric or photometric quantities.
- In the optical setup (OS) we have prepared two Universal Detectors for that purpose. One for the general pattern impression and one for a detail of it.
- Here we configure the detection of the radiometric quantity "Irradiance" which is derived from the Poynting vector.
- As a consequence all 6 EM field components have to be evaluated to calculate the Poynting vector and then the irradiance.
- For such a paraxial system, the summed squared amplitudes and the irradiance result are proportional.

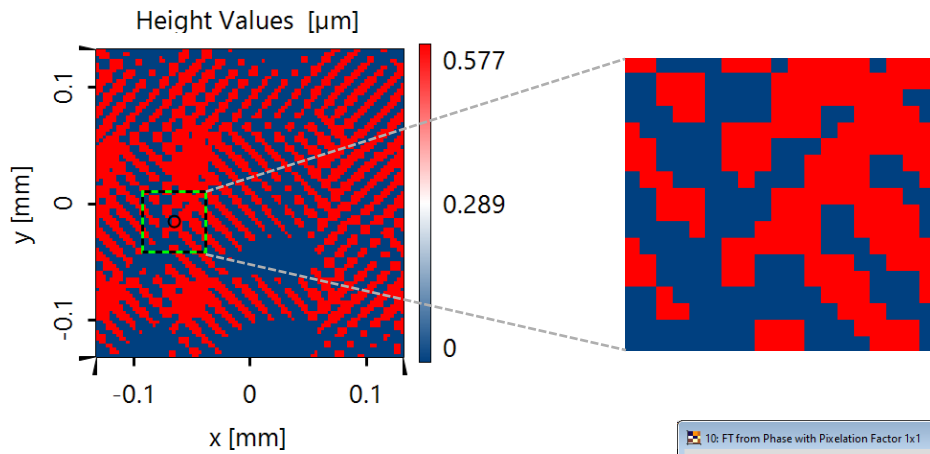


Simulate Pixelated DOE

- The first system simulations neglected the pixelated nature of the phase or height distribution.
- By introducing a pixelation factor larger than 1×1 per we "tell" VLF to sample each phase (and structure) pixel (respectively) by multiple points.



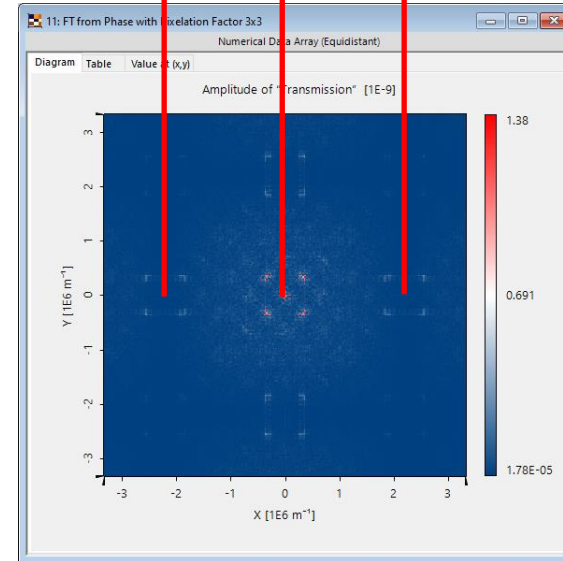
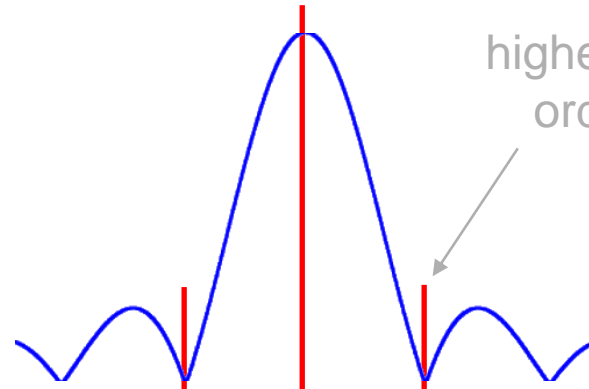
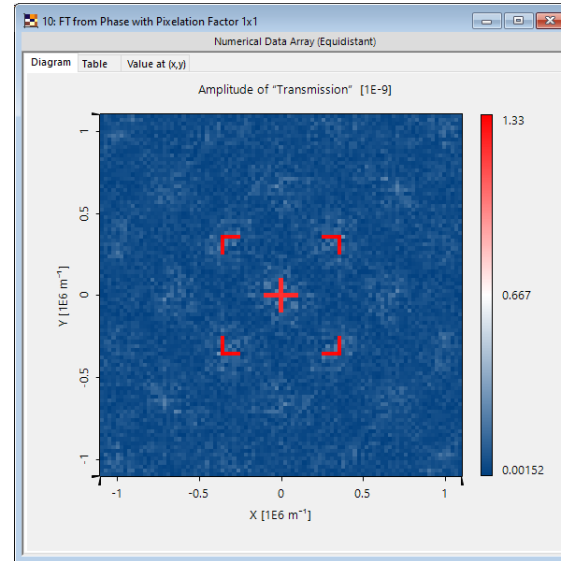
Higher Sinc Orders Due to Structure Pixelation



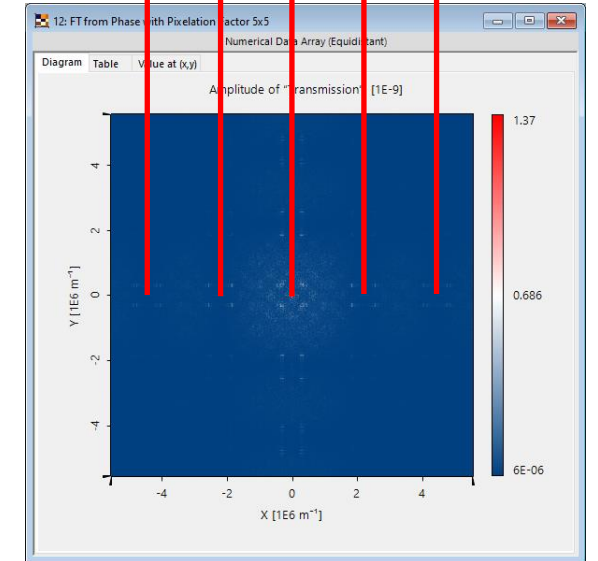
When light interacts with equidistant rectangular height plateaus (pixels), the generated diffraction order energies are globally modulated according to a sinusoidal function.

And the equidistance represents an additional period, which yields the so-called higher sinc diffraction orders.

The IFTA design counteracts the unwanted sinc modulation.

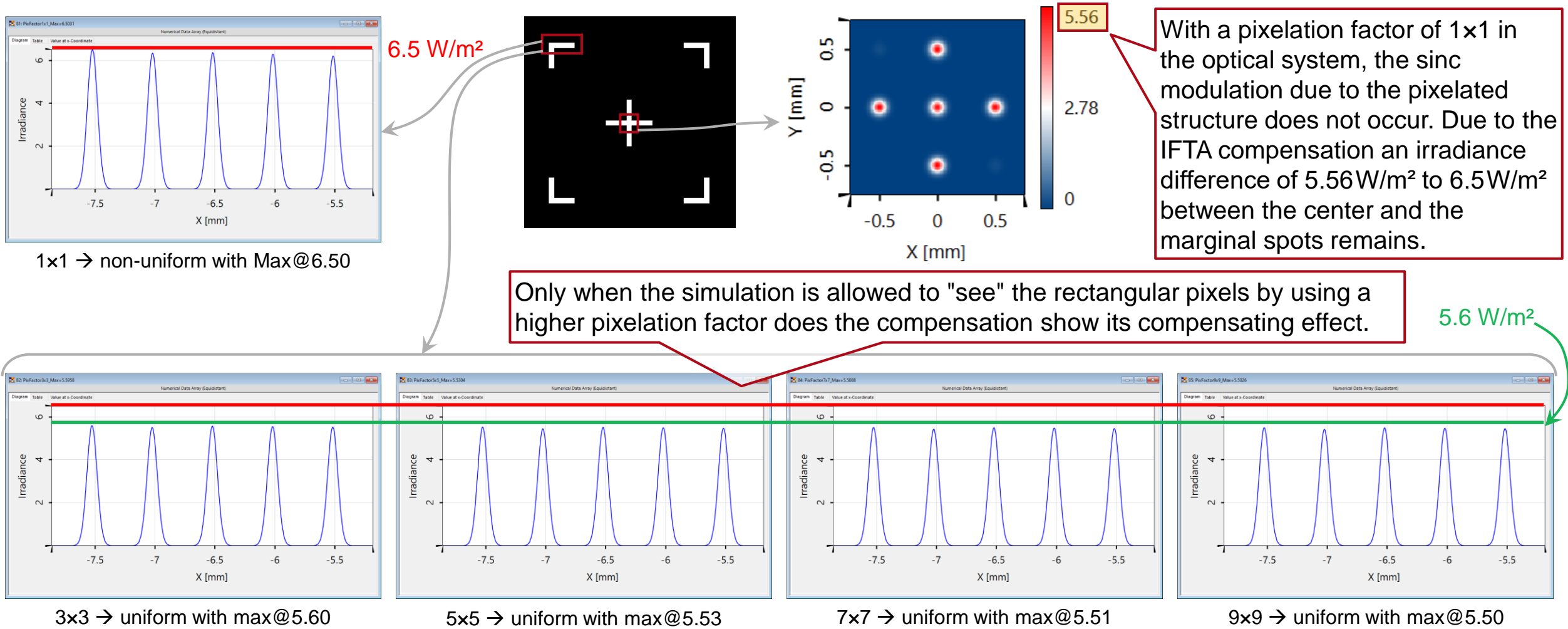


output field size x 3



output field size x 5

Convergence Check for Pixelation Factor



The difference of the maximum value between the simulation with a pixelation factor of 5×5 and 9×9 is only 0.5%. It is a question of compromise between accuracy and calculation time.